

METHOD FOR ETCHING SMOOTH SIDEWALLS IN III-V BASED COMPOUNDS FOR ELECTRO-OPTICAL DEVICES

ABSTRACT

5 III-V based compounds are etched to produce smooth sidewalls for electro-optical applications using BCl_3 together with chemistries of CH_4 and H_2 in RIE and/or ICP systems. HI or IBr or some combination of group VII gaseous species (Br, F, I) may be added in accordance with the invention.

10 Fig. 1